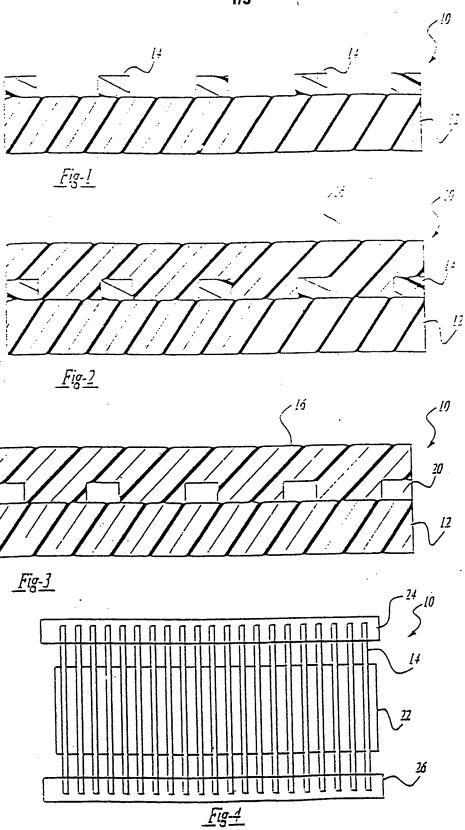
Title: PROCESS FOR FABRICATING A SEMICONDUCTOR DIFFRACTION GRATING USING A SACRIFICIAL LAYER

Inventor(s): Michael P. Nesnidal et al. Attorney Docket No. NGC-00087DA (11-0983D)

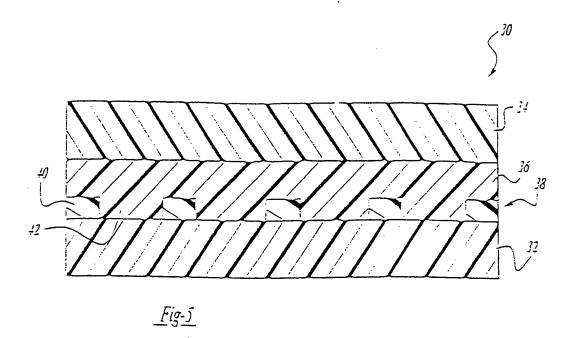
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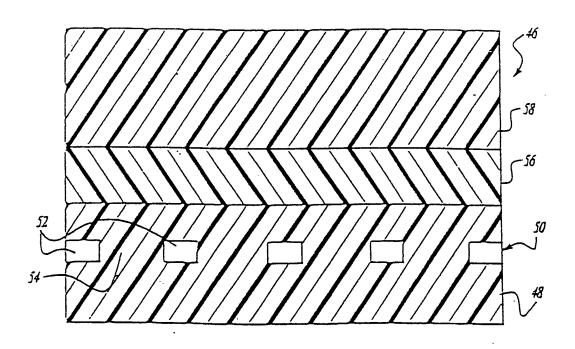


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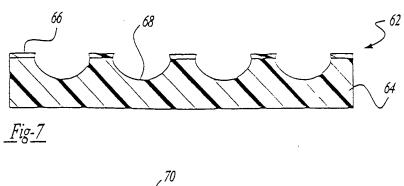


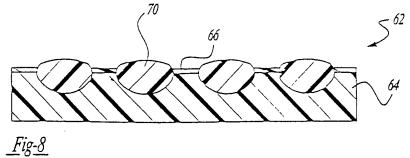
<u>Fig-6</u>

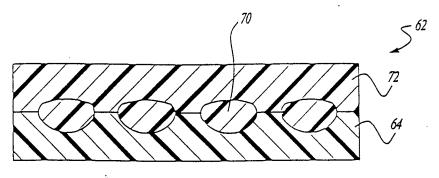
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<u>Fig-9</u>

